

USHIO gains market share in EUV Source Business

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I missed the announcement of USHIO's acquisition of Philips Extreme, so I asked Marc Corthout, President of Philips Extreme, about it. He said that Philips Lighting is fully focusing its future on mainstream solid state lighting (LED-based), while USHIO (and its full subsidiary, Xtreme technologies) is very much concentrating on business-to-business lighting and has a large stake already in light sources for optical lithography through its I line business and its share in Gigaphoton.

Therefore, Philips as the original driver of Sn DPP technology has decided to help USHIO/Xtreme take business ownership of this technology by transferring the technological know-how and related people to where they are needed, Marc said.

This is not the end of Sn DPP technology but more the start of its further growth, which can be illustrated by two examples: Philips spun out its optical lithography 25 years ago, creating ASML, and launched TSMC in partnership with the Taiwanese government, later stepping out of the foundry business. In both cases, major independent businesses were created that brought financial value to Philips.

I see this move as giving USHIO further dominance in the lithography light source market. The main suppliers to the 193 nm excimer market are Cymer and Gigaphoton, which is jointly owned by Komatsu and USHIO. In the EUV Source market, current suppliers are Cymer, Gigaphoton and USHIO (which bought Xtreme technologies prior to its Philips acquisition). Today, working sources in the field are based on DPP technology. Xe DPP sources from Xtreme technologies are used in MET tools and Sn DPP sources from Philips Extreme are being utilized in ADT. So this move makes USHIO responsible for all high power EUV sources in the field, and allows it to be present in both DPP and LPP markets (via Gigaphoton) for EUV sources.

